	Hits	Search Text	DBs
29	11	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and ((immers$4 near9 (liquid or fluid)) same ((capillary near9 force) or capillarit$3 or capillary) same (contact$4 or prevent$4 or flatten$4 or area or pressure) same (workpiece or substrate or target or wafer))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
30	16	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((immers$4 near9 (liquid or fluid or medium)) same ((capillary near9 force) or capillarit$3 or capillary) same (contact$4 or prevent$4 or flatten$4 or area or pressure) same (workpiece or substrate or target or wafer))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
31	3	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and ((immers$4 near9 (liquid or fluid)) same ((capillary near9 force) or capillarit$3) same (contact$4 or prevent$4 or flatten$4) same (workpiece or substrate or target or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
33	11	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and ((immers$4 near9 (liquid or fluid)) same ((capillary near9 force) or capillarit$3 or capillary) same (contact$4 or prevent$4 or flatten$4 or area or pressure) same (workpiece or substrate or target or wafer))	US-PGPUB

	Hit s	Search Text	DBs
34	41	((immersion near14 lithography) or ((liquid or fluid or medium) near9 immersion near14 (system or apparatus or method))) and ((immers$4 near9 (liquid or fluid or medium)) same ((capillary near9 force) or capillarit$3 or capillary) same (workpiece or substrate or target or wafer))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
35	0	355/77.ccls. and ((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi$3 near6 (fluid$4 or liquid or medium))) and (modulat$4 or (spatial near14 modulat$4) or SLM) and (expos$4 or illuminat$4 or irradiat$4) and ((mask or reticle or photomask) same pattern$4) and ((lens or optics) near12 (inlet or port or passage) near18 (immersion or fluid or liquid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
36	0	355/53.ccls. and ((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi$3 near6 (fluid$4 or liquid or medium))) and (modulat$4 or (spatial near14 modulat$4) or SLM) and (expos$4 or illuminat$4 or irradiat$4) and ((mask or reticle or photomask) same pattern$4) and ((lens or optics) near12 (inlet or port or passage) near18 (immersion or fluid or liquid))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
37	0	355/77.ccls. and ((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi$3 near6 (fluid$4 or liquid or medium))) and (modulat$4 or (spatial near14 modulat$4) or SLM) and (expos$4 or illuminat$4 or irradiat$4) and ((mask or reticle or photomask) same pattern$4) and ((lens or optics) near12 (inlet or port or passage) near18 (immersion or fluid or liquid))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
38	0	430/322.ccls. and ((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi$3 near6 (fluid$4 or liquid or medium))) and (modulat$4 or (spatial near14 modulat$4) or SLM) and (expos$4 or illuminat$4 or irradiat$4) and ((mask or reticle or photomask) same pattern$4) and ((lens or optics) near12 (inlet or port or passage or nozzle) near18 (immersion or fluid or liquid))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
39	0	355/53.ccls. and ((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi$3 near6 (fluid$4 or liquid or medium))) and (modulat$4 or (spatial near14 modulat$4) or SLM) and (expos$4 or illuminat$4 or irradiat$4) and ((mask or reticle or photomask) same pattern$4) and ((lens or optics) near12 (inlet or port or passage) near18 (immersion or fluid or liquid))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
40	0	355/18.ccls. and ((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi$3 near6 (fluid$4 or liquid or medium))) and (modulat$4 or (spatial near14 modulat$4) or SLM) and (expos$4 or illuminat$4 or irradiat$4) and ((mask or reticle or photomask) same pattern$4) and ((lens or optics) near12 (inlet or port or passage) near18 (immersion or fluid or liquid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
41	1	355/18.ccls. and ((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi$3 near6 (fluid$4 or liquid or medium))) and (modulat$4 or (spatial near14 modulat$4) or SLM) and (expos$4 or illuminat$4 or irradiat$4) and ((mask or reticle or photomask) same pattern$4) and ((lens or optics) near12 (capillary) near18 (immersion or fluid or liquid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB